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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Karola Richter et al.

Serial No:

Art Unit:

Filing Date:

Title: SILICON SUBSTRATE COMPRISING POSITIVE ETCHING  
PROFILES WITH A DEFINED SLOPE ANGLE, AND  
PRODUCTION METHOD

Examiner:

Priority Applications: Country: Germany; No.: 103 18 568.2; Filing Date:  
April 15, 2003

PCT Application: No.: PCT/DE2004/000804 Filing Date: April 15, 2004

October 14, 2005

Attorney's Docket No.: HMP201A1

**PRELIMINARY AMENDMENT**

Hon. Commissioner of Patents and Trademarks

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SIR:

This is a preliminary amendment to provide certain corrections in the above captioned patent application. The applicants petition that, if required, the time for response be extended and the corresponding fee be charged. The Commissioner is hereby authorized to charge any additional fees which may be required to Acct. No. 11-0224. The Applicants further respectfully request that this response be accepted as a bona fide effort to meet any potential response requirements outstanding and due in the above captioned matter. Please amend the application as follows: